



OPT – S6000

OPTIONS

NEW

- COMBINED OPTICAL PROFILER**
- Wavelengths 470 nm, 532 nm, 635 nm, 650 nm, 785 nm, 1064 nm, 1310 nm**
- Micro Spotsize**
- Wafer Mapping**
- Automated Angle of Incidence 20-90°**
- Motorized XY stage**
- Liquid Cell**
- CCD image camera**
- Heater**

OPT-S6000 multi-wavelength ellipsometer use multiple fixed lasers as the light source with 2-5 selective discrete wavelengths by modular design method. It provides more data to meet the needs of the user to detect complex samples.

STANDARD FEATURES

- **Excellent accuracy and repetition**
- **Widest variable angle range (20°-90°)**
- **Multiple wavelengths to provide more information**
- **Auto change wavelength for easy operation**
- **A second laser for easy alignment and accuracy**
- **User friendly software and materials library**
- **Hundreds of materials information in material library.**

TECHNICAL SPECIFICATIONS

Wavelengths	<i>470 nm, 532 nm , 635 nm , 650 nm, 785 nm, 1064 nm, 1310 nm or other solid state lasers can be provided</i>
Thickness range of transparent films	<i>0 - 6000 nm</i>
Thickness range of absorptive films	<i>0 - 6000 nm</i>
Accuracy of ellipsometric parameters	<i>$tg(\varphi) \leq 0.01, \cos(\Delta) \leq 0.0001$</i>
Accuracy of film thickness measurement	<i>$\pm 0.0001 \text{ nm}$ for SiO_2 standard sample</i>
Stability Long Term (months)	<i>$\pm 0.01^\circ$</i>
Measurement time	<i>less than 1 sec</i>
Sample Alignment	<i>Second laser alignment with automatic correction unit</i>
Sample stage adjustments	<i>Tilt and height</i>
Size of the sample stage	<i>$\varnothing 160 \text{ mm}$</i>
Range of angle	<i>20 – 90°</i>
Angle steps	<i>$5^\circ \pm 0.01$</i>